

Polymers for Microelectronics

Science and Technology

Edited by
Y. Tabata, I. Mita, S. Nonogaki,
K. Horie, S. Tagawa

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Edited by

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Preface

Polymers have played an important role in the development of microelectronics and are becoming ever more important for the future of microelectronics. The most important recent progress in the polymers for microelectronics, especially with regard to resist materials, was presented and discussed at "Polymers for Microelectronics (PME '89) – Science and Technology –" the first international symposium in this field to be held in Japan. About 300 researchers (70 from abroad and 230 Japanese) from all over the world attended PME '89.

This volume has been organized into three sections: fundamental and applied research on resists and related compounds, polyimides and related functional polymers for electronics, and new photoresponsive polymers for optical memory and related applications. All papers were reviewed by referees.

We are indebted to many individuals and organizations for making PME '89 possible, especially the Organizing Committee, the members of the Steering Committee, who did so much to make PME '89 run smoothly, and the members of the secretariat.

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